IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No	10813543
Filing Date	March 3, 2004
Confirmation No.	
Inventor	Gealv. F. Daniel
Assignee	Micron Technology, Inc.
Group Art Unit	
Examiner	Chen, Keath T.
Attorney's Docket No	MI22-3685
Title: Method for Reducing Physisorption During Atomic Layer Deposition	

INFORMATION DISCLOSURE STATEMENT

References - - See attached Form PTO/SB/08

The attached Form PTO/SB/08 is submitted in compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, and your attention is directed to the references listed on the attached Form PTO/SB/08. No admission is made regarding whether the submitted references are prior art.

A fee in the amount of \$180.00 will be paid to cover the fee specified under 37 C.F.R. § 1.17(p).

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 6/38/08

Зу: _

Robert C. Hyta Reg. No. 46791